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Docket No.: 4425-168

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of	:	<u><b>BOX OFFICIAL DRAFTSMAN</b></u>
	:	
LU, YEN-TING	:	<i>Confirmation No. 4176</i>
	:	
U.S. Patent Application No. 09/919,868	:	Group Art Unit: 1756
	:	Allowed: February 11, 2004
Filed: August 2, 2001	:	Examiner: Christopher G. Young

For: **METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST**

**LETTER SUBMITTING FORMAL DRAWINGS**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Submitted herewith are 6 sheets of Replacement Formal Drawings in connection with the above referenced application.

Respectfully submitted,

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